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Phosphorus Implant in Silicon - Depth profile

Art. ID	NIST-2133
Unit	each
Deliverydetails	No Dangerous Good /not restricted

Description

This Standard Reference Material (SRM®) is intended for use in calibrating secondary ion response to minor and trace levels of phosphorus in a silicon matrix by the analytical technique of secondary ion mass spectrometry (SIMS). NIST-2133 is intended for calibrating the response of a SIMS instrument for phosphorus in a silicon matrix under a specific set of instrumental conditions. It may also be used by a laboratory as a transfer standard for the calibration of working standards of phosphorus in silicon. This SRM consists of a 1 cm × 1 cm single crystal silicon substrate that has been ion-implanted with the isotope 31 P at a nominal energy of 100 keV. /// Sample value(s) - please ask for current certificate.

Text/Information	Analyte/Parameter	CAS number	Concentration/Value	Unit	Method	Source
	Retained dose of 31P		0.04927 ± 0.00083	µg/cm2		